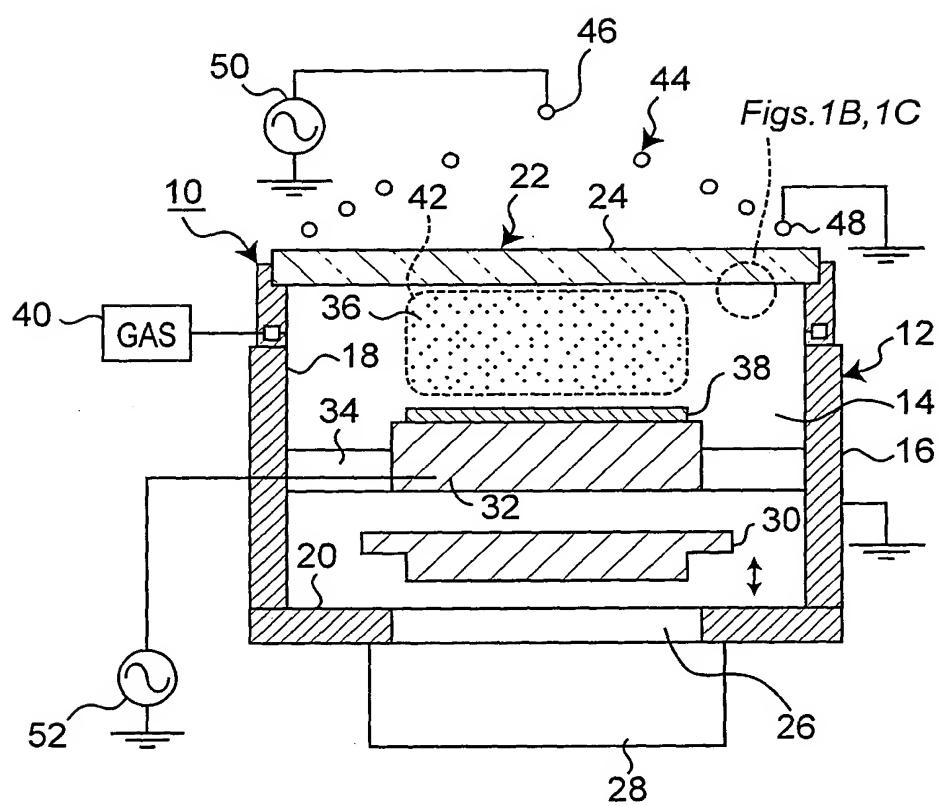
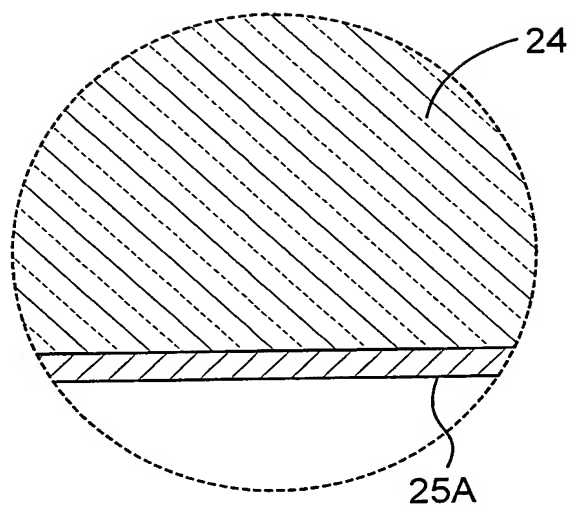


*Fig. 1A*





*Fig. 1B*



*Fig. 1C*

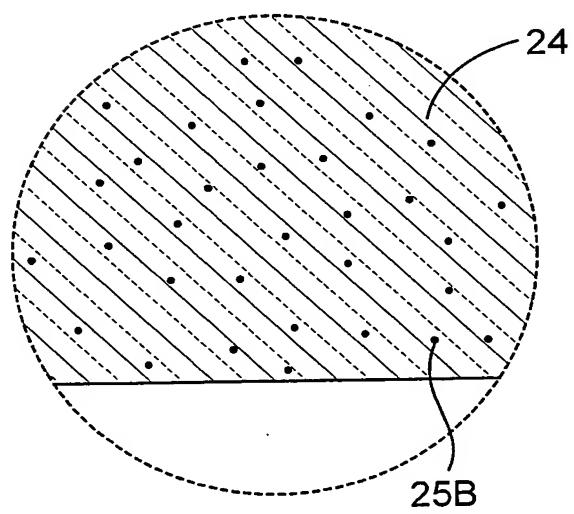




Fig. 2

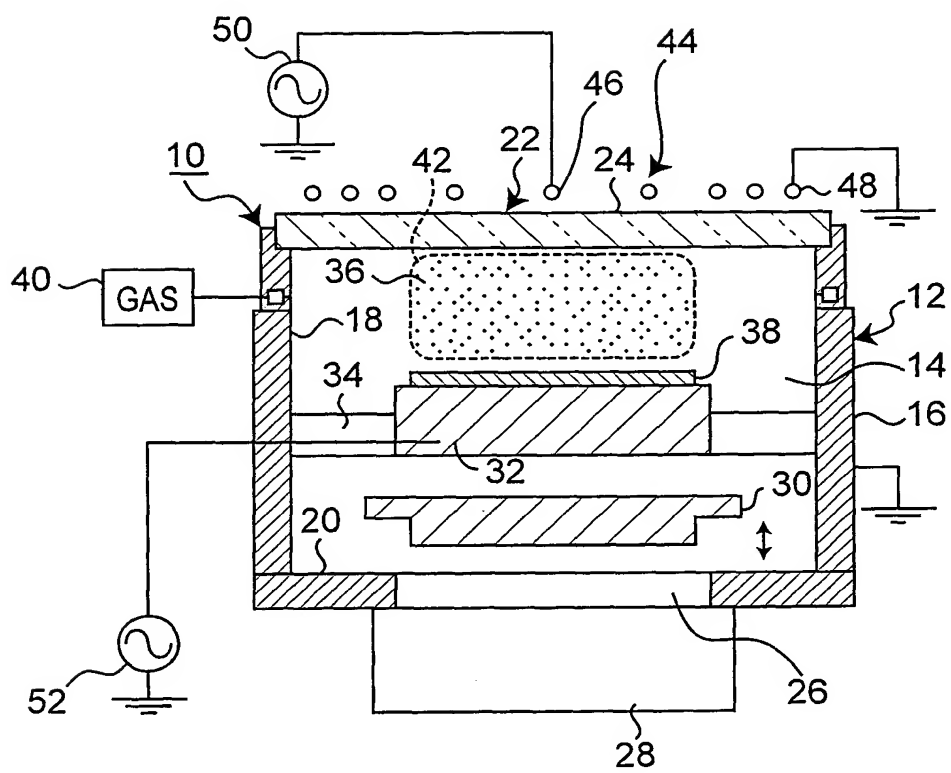




Fig.3

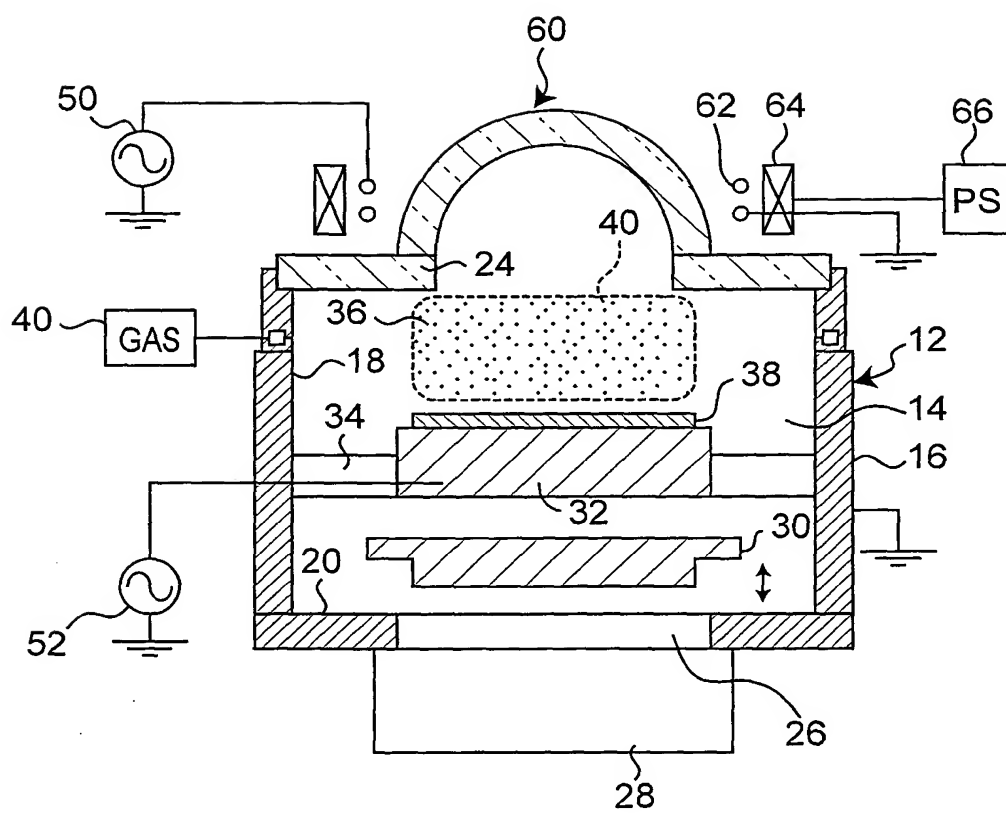




Fig. 4

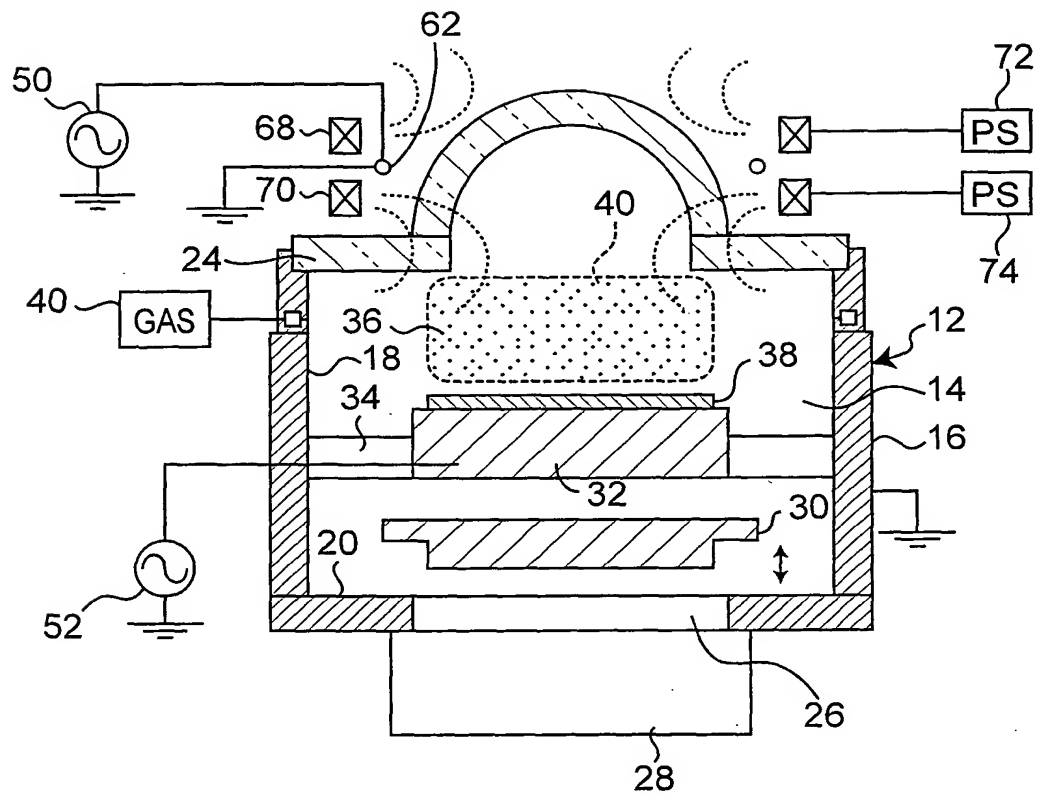
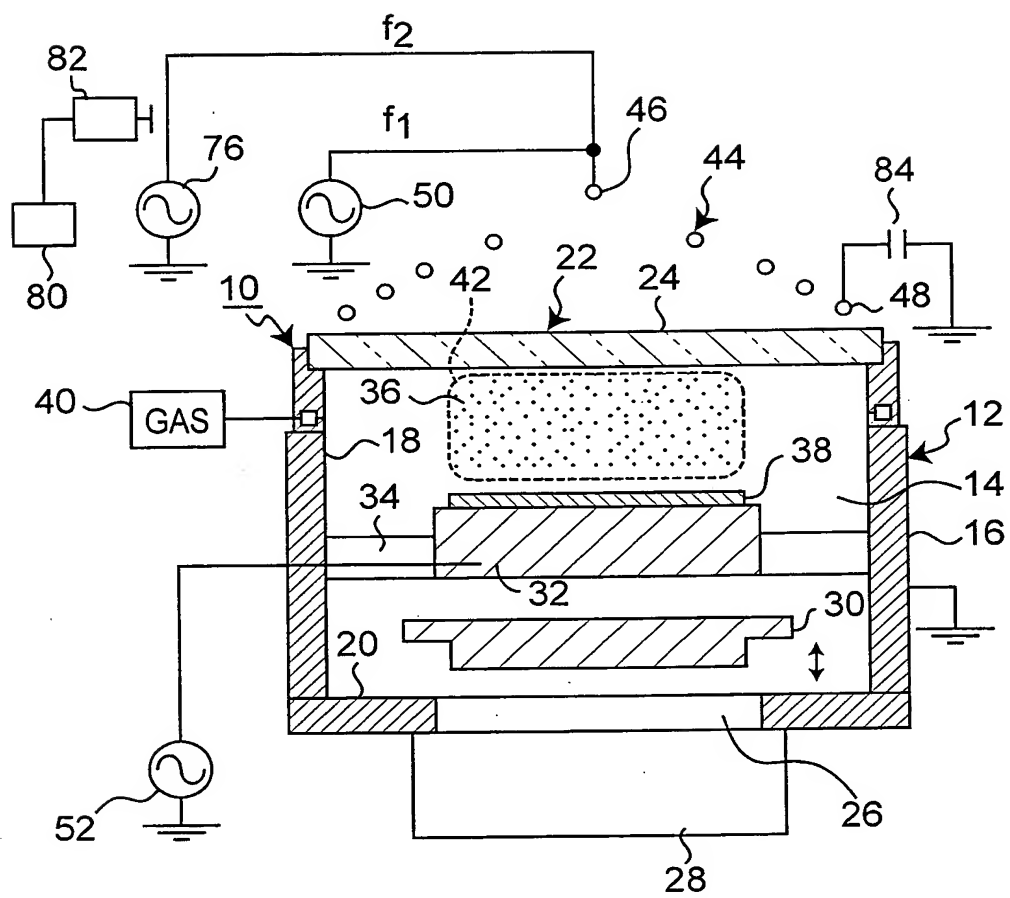




Fig. 5





The diagram illustrates a plasma processing apparatus. It features a main chamber (12) with a side wall (14) and a bottom flange (16). Inside the chamber, there is a substrate (20) supported by a pedestal (26). A gas inlet (40) is connected to the chamber, and a gas flow control system (80, 82, 46, 44, 48, 50) is connected to the chamber. A power supply (52) is connected to the substrate. A plasma source (90) is located above the chamber. The chamber is labeled with various components: 12, 14, 16, 18, 24, 30, 32, 34, 36, 38, 42, 50, 52, 80, 82, 90, 92.

g.6B

90



Fig. 7

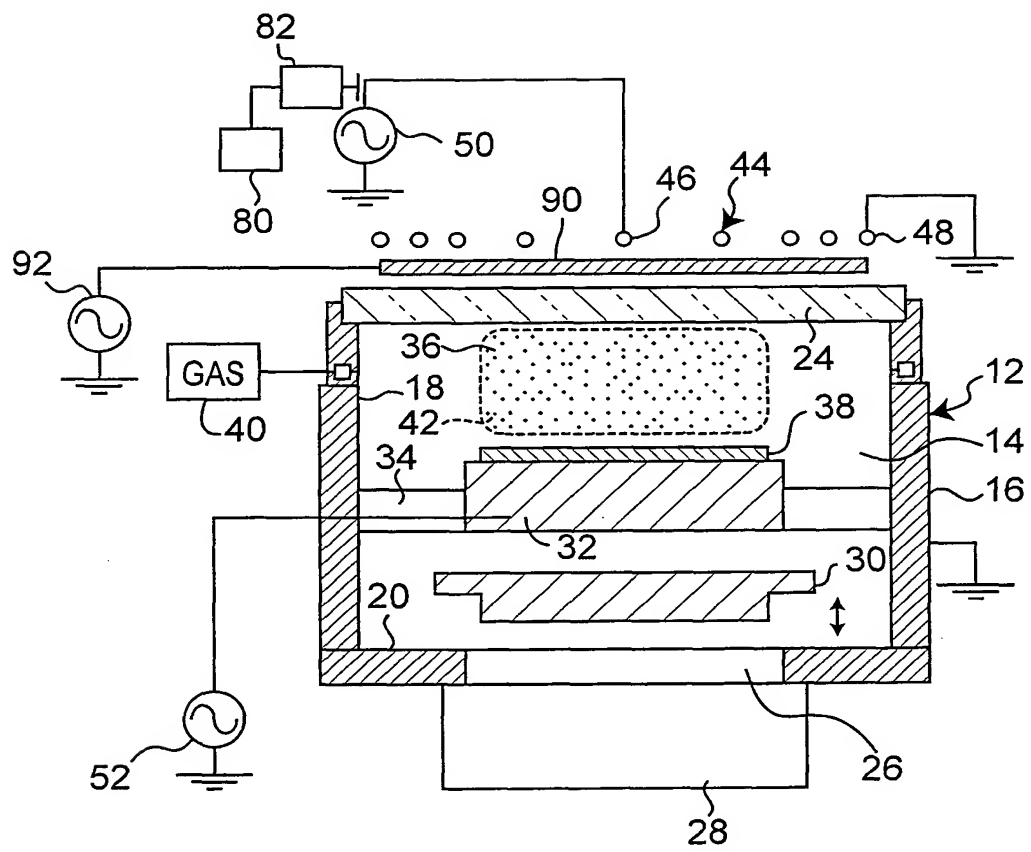




Fig. 8A

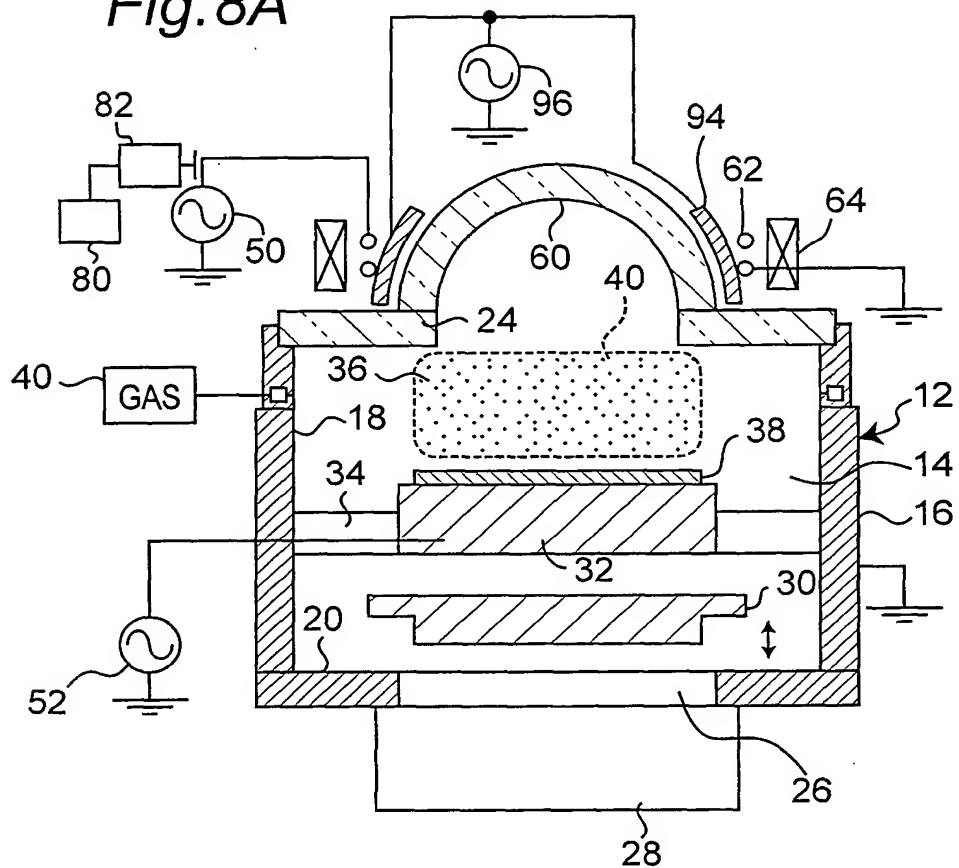


Fig. 8B

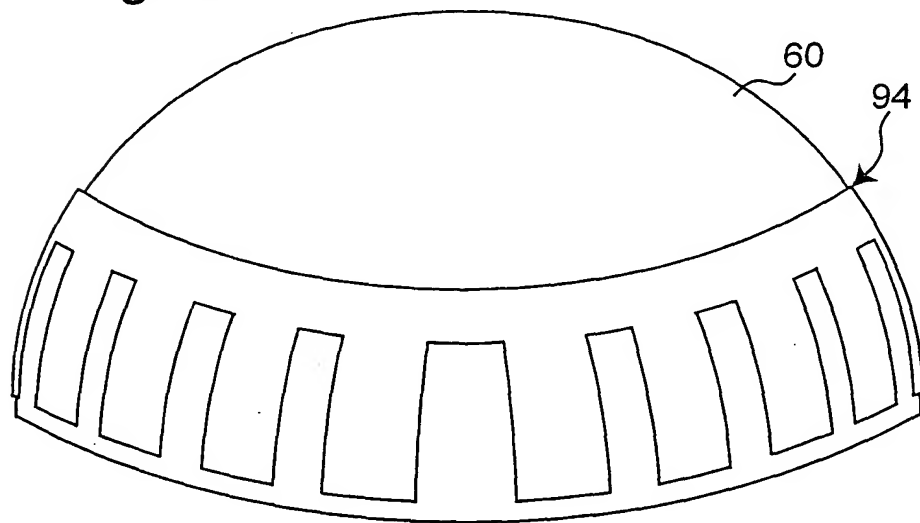




Fig. 9

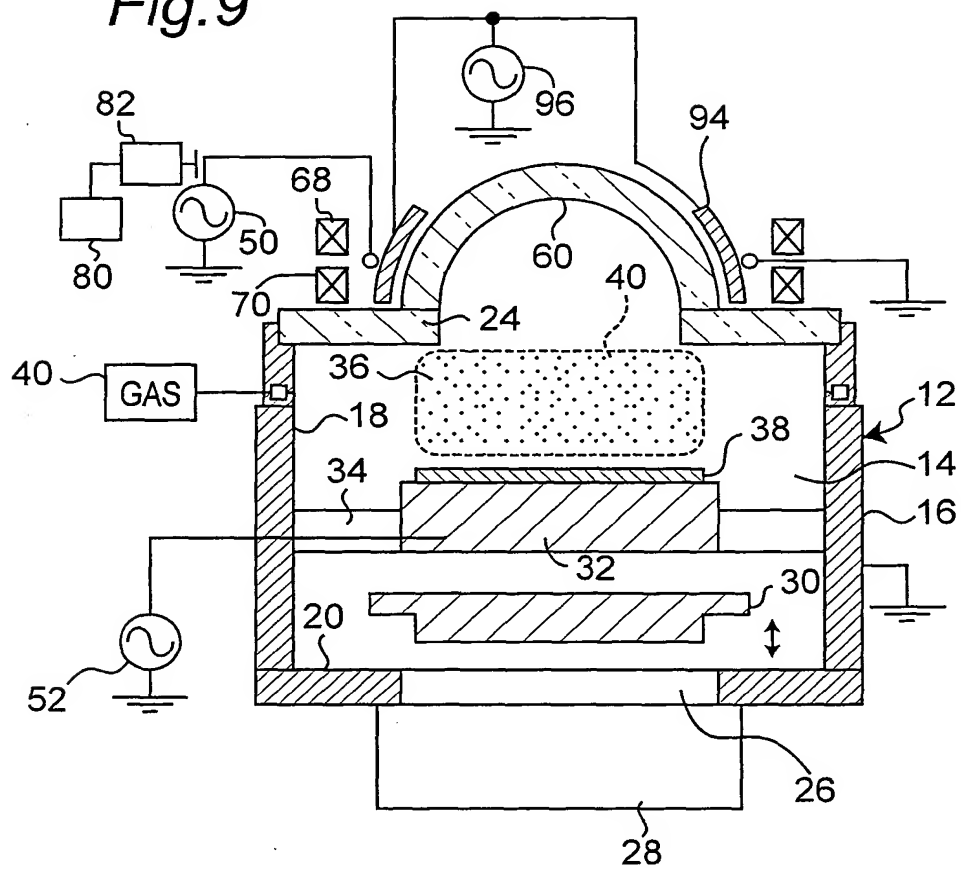
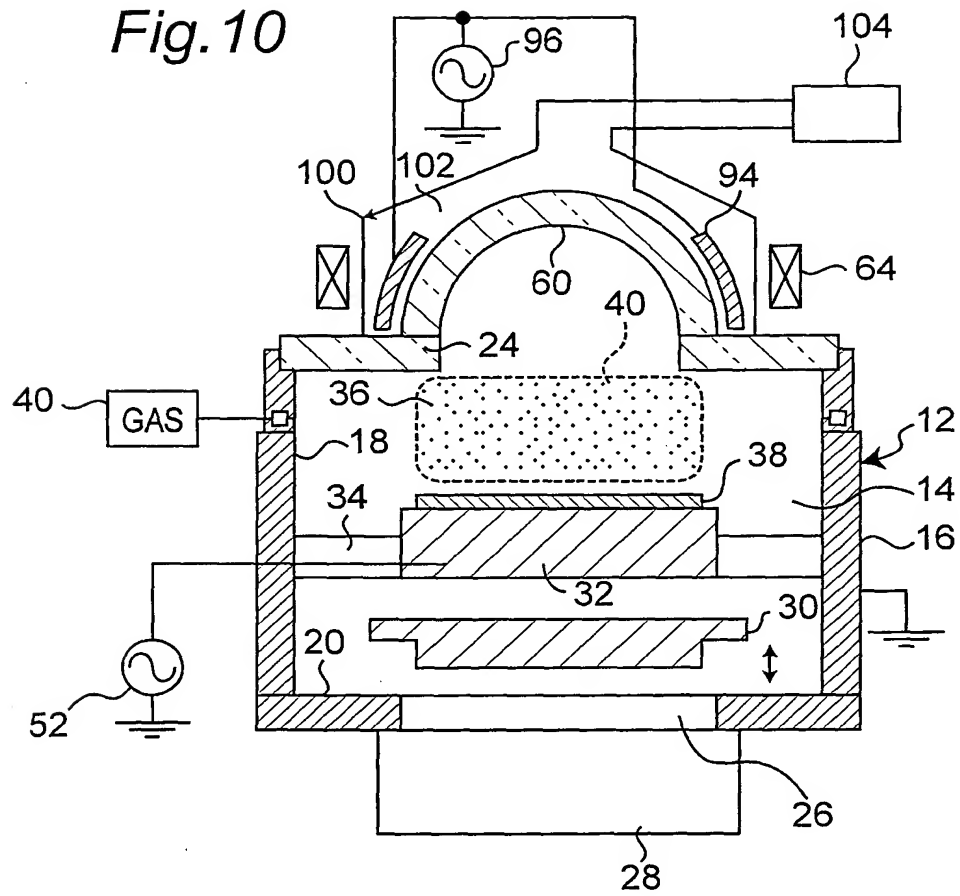




Fig. 10





*Fig. 11*

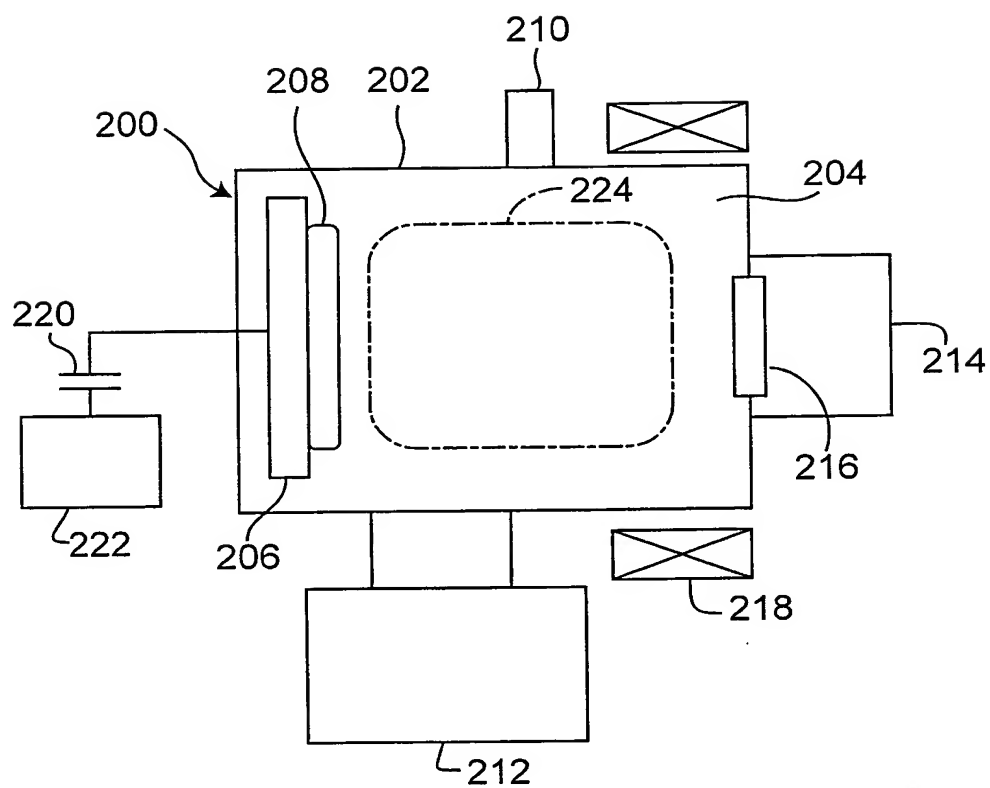




Fig. 12

